

SPUTTERING TARGET FOR MAGNETIC RECORDING MEDIUM
ABSTRACT

A sintered compact sputtering target having an Fe-Pt alloy and nonmagnetic material(s) as its main components, wherein the sintered compact sputtering target contains at least C (carbon) as the nonmagnetic material, and additionally contains trace additive element(s) other than the main components in an amount of 50 massppm to 5000 massppm, and a standard free energy ΔG° for the formation of a carbide of each trace additive element is -5000 [cal/mol] or less per 1 mol of carbon in the carbide. The present invention aims to provide a sputtering target having an Fe-Pt-based alloy and nonmagnetic material(s) as its main components, which can considerably reduce the amount of particles to be generated during sputtering.